

	Hits	Search Text	DBs
26	43	<p>((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same          (photo\$4active\$4acid\$4generat\$4 or (photoacid near5 generat\$4) or (acid near5 generat\$4)) same          (thin\$4 or etch\$4)) and          ((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4) same          (concentration or amount or increas\$4 or var\$5 or chang\$4) same (expos\$4 or irradiat\$\$ or illuminat\$4) same (ion\$5 or e\$3beam or (electron near4 beam) or X\$4ray or EUV)) and ((resist or photoresist or photosensitive) same (fluorine or bismuth or cesium or antimony or fluoro\$3polymer\$4 or (metalloce\$4 near9 polymer\$3) or (chelate near6 polymer\$6) or F\$2 or Bi or Cs or Sb or Sn or tin)) and ((resist or photoresist) same (PHS or polyhydroxystyrene)) and (X\$2ray or (secondary near6 electron))</p>	US - PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
27	52	((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same (photo\$4active\$4acid\$4generat\$4 or (photoacid near5 generat\$4) or (acid near5 generat\$4)) same (thin\$4 or etch\$4)) and ((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4) same (concentration or amount or increas\$4 or var\$5 or chang\$4) same (expos\$4 or irradiat\$\$ or illuminat\$4) same (ion\$5 or e\$3beam or (electron near4 beam) or X\$4ray or EUV)) and ((resist or photoresist or photosensitive) same (fluorine or bismuth or cesium or antimony or fluoro\$3polymer\$4 or (metalloce\$4 near9 polymer\$3) or (chelate near6 polymer\$6) or F\$2 or Bi or "Cs" or Sb or Sn or tin) same (add\$5 or incorporat\$4 or introduc\$4)) and ((resist or photoresist) same (PHS or polyhydroxystyrene))	US-PPGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	30	<p>((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same          (photo\$4active\$4acid\$4generat\$4 or (photoacid near5 generat\$4) or (acid near5 generat\$4)) same          (thin\$4 or etch\$4)) and          ((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4) same          (concentration or amount or increas\$4 or var\$5 or chang\$4) same (expos\$4 or irradiat\$\$ or illuminat\$4) same (ion\$5 or e\$3beam or (electron near4 beam) or X\$4ray or EUV)) and ((resist or photoresist or photosensitive) same (fluorine or bismuth or cesium or antimony or fluoro\$3polymer\$4 or (metalloce\$4 near9 polymer\$3) or (chelate near6 polymer\$6) or F\$2 or Bi or "Cs" or Sb or Sn or tin) same          (add\$5 or incorporat\$4 or introduc\$4)) and ((resist or photoresist) same (PHS or polyhydroxystyrene)) and          (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron))</p>	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
29	48	((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same (photo\$4active\$4acid\$4generat\$4 or (photoacid near5 generat\$4) or (acid near5 generat\$4)) same (thin\$4 or etch\$4)) and ((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4) same (concentration or amount or increas\$4 or var\$5 or chang\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoresist or photosensitive) same (fluorine or bismuth or cesium or antimony or fluoro\$3polymer\$4 or (metalloce\$4 near9 polymer\$3) or (chelate near6 polymer\$6) or F\$2 or Bi or "Cs" or Sb or Sn or tin) same (add\$5 or incorporat\$4 or introduc\$4)) and ((resist or photoresist) same (PHS or polyhydroxystyrene)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron))	US - PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	18	S33 NOT S32	US - PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	6	((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4)) and ((resist or photoresist or photosensitive) same (fluorine or bismuth or cesium or antimony or fluoro\$3polymer\$4 or (metalloce\$4 near9 polymer\$3) or (chelate near6 polymer\$6) or F\$2 or Bi or "Cs" or Sb or Sn or tin) near26 (add\$5 or incorporat\$4 or introduc\$4 or enhanc\$4 or includ\$4)) and ((resist or photoresist) same (PHS or polyhydroxystyrene)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4) near6 thick\$5)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

Hits	Search Text	DBs
32 5	((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4)) and ((resist or photoresist or photosensitive) same (fluor or fluoro\$3polymer\$4 or (metalloce\$4 near9 polymer\$3) or metal\$5) near28 (add\$5 or incorporat\$4 or introduc\$4 or enhanc\$4 or includ\$4)) and ((resist or photoresist) same (PHS or polyhydroxystyrene)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4) near6 thick\$5)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
33 15	((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4)) and ((resist or photoresist or photosensitive) near22 (fluor or fluoro\$6poly\$6 or (metalloce\$4 near9 polymer\$3) or metal\$5) near28 (add\$5 or incorporat\$4 or introduc\$4 or includ\$4)) and ((resist or photoresist) same (PHS or polyhydroxystyrene)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
34	12	S37 NOT S36	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB